RESPONSE UNDER 37 C.F.R. § 1.111

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where the X is -O-, -S-, $-C(CF_3)_2$ -, $-C(CH_3)_2$ -, -CO-, $-CH_2$ -, -NHCO-, $-SO_2$ -, -SO-, or a bond, and **n** is an integer from 10 to 100.

The Examiner interprets Varnish A and Varnish B disclosed in TOMIKAWA et al. as the compound of the present application. Varnish A and Varnish B include a poly(imidebenzoxazole) precursor and a naphthoquinonediazide compound. The poly(imidebenzoxazole) precursor of TOMIKAWA et al. is a dianhydride monomer (n=1), as disclosed in the Synthesis Example 5 of TOMIKAWA et al., rather than a polymer; however, the poly(imidebenzoxazole) precursor of the present application must be a polymer (n=10~100). Therefore, the positive photosensitive composition of the present application is novel over TOMIKAWA et al. and it is Applicant's belief that the 102(e) rejection should be withdrawn.

TOMIKAWA et al. does not teach or suggest the poly(imide-benzoxazole) precursor of the present application. TOMIKAWA et al. does disclose several NQDs; however, these NQDs are not the main feature of the present application. In addition, the pattern made by the method of pattern formation using the positive photosensitive composition of the present application has the advantages of thermal stability, high intensity, and excellent resolution. See lines 3-14 of page 3 in the specification. These advantages are not taught or suggested by TOMIKAWA et al.,

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which only teaches that the composition and method are for low film loss in unexposed regions.

Respectfully submitted,

Registration No. 32,765

It is, therefore, Applicant's belief that claims 1-33 are allowable over the cited reference.

Allowance is respectfully requested.

SUGHRUE MION, PLLC

Telephone: (202) 293-7060

Facsimile: (202) 293-7860

washington office 23373

CUSTOMER NUMBER

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